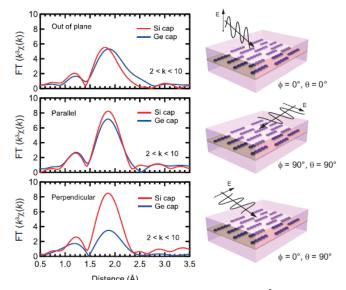
## Introduction of wired-heavy metal dopants into Si substrates

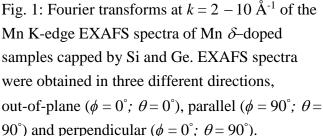
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A dopant makes localized electronic state useful for a laser, an electronic device and so on. 1D dopants rather than a lone dopants have advantages: reduction of alloy scattering in electronic devices; useful structure for quantum information platform; and etc. Recently we succeeded in introduction of wired-heavy metal dopants such as wired-Mn or wired-Bi dopants into Si substrates<sup>1,2,3</sup>.

As the first example, we realized Mn  $\delta$ -doping into Si/Si and Si/Ge interfaces by using Mn atomic chains on Si(001) as a starting material<sup>1</sup>. Encapsulation of the Mn chains of 0.5ML (defined with an atom density of  $6.8 \times 10^{14}$  atoms cm<sup>-2</sup> on Si(001) surface as 1ML) with a growth of Si or Ge capping layer at room temperature avoids either the formation of silicides or





germanides. We characterized the local structure around the Mn atoms by employing highly sensitive X-ray absorption fine structure measurements at Spring-8 BL37XU. The obtained results for the Ge capping case showed anisotropic profiles of its radius atomic function in case the incident X-ray polarization is normal or parallel to the Mn chain, as show in Fig. 1 (middle and bottom). It means that Mn dopants have 1 dimensional structure even after its burial at Ge/Si interface. Independently we studied the hall measurement of the Ge/Mn chain/Si(001) and it was found that Mn acts as a p-type dopant. Therefore, we strongly infer that 1D Mn dopants at the Ge/Si interface could be obtained. The density functional theory calculation of the corresponding model supports our analysis.

I would also introduce the other case of the wired-Bi dopants in Si crystal in my talk<sup>2,3</sup>.

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## References:

- 1. Koichi Murata, Christopher Kirkham, Satoshi Tsubomatsu, Takashi Kanazawa, Kiyofumi Nitta, Yasuko Terada, Tomoya Uruga, Koh-ichi Nittoh, David R Bowler and Kazushi Miki, appears soon in Nanoscale.
- 2. Koichi Murata, Kazushi Miki, and Susumu Fukatsu, Appl. Phys. Lett. 111 (2017) 152104.
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